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		Application Number	
		Filing Date	Concurrently Herewith
		First Named Inventor	Cesar M. Garza <i>et al.</i>
		Group Art Unit	
Examiner Name		Attorney Docket Number	SC12879TP

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number -Kind Code ² (if known)			
	AA	6,245,489 B1	06/12/2001	Baklanov <i>et al.</i>	
	AB	US2003/0118935 A1	06/26/2003	Matsuzawa	

FOREIGN PATENT DOCUMENTS						
Examine r Initials*	Cite No. ¹	Foreign Patent Document		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	AC	Kudo <i>et al.</i> , "CD Changes of 193nm Resist During SEM Measurement," <i>Advances in Resist Technology and Processing XVIII</i> , Francis M. Houlihan, Editor, <i>Proceedings of SPIE</i> , 2001, Vol. 4345, pp. 179-189.	
	AD	Vasconi <i>et al.</i> , "193nm Metrology: facing severe e-beam/resist interaction phenomena," <i>Metrology, Inspection, and Process Control for Microlithography XV</i> , Neal T. Sullivan, Editor, <i>Proceedings of SPIE</i> , 2001, Vol. 4344, pp. 653-661.	
	AE	Wu <i>et al.</i> , "Investigation on the Mechanism of the 193nm Resist Linewidth Reduction During the SEM Measurement," <i>Advances in Resist Technology and Processing XVIII</i> , Francis M. Houlihan, Editor, <i>Proceedings of SPIE</i> , 2001, Vol. 4345, pp. 190-199.	

Examiner Signature		Date Considered	
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